

**Amendments to the Specification:**

Please amend the third paragraph on page 1 as follows:

~~US Patent 5,671,054 discloses a method and an apparatus for determining the position of patterns on substrates that have a specific thickness. The substrate is placed onto a measurement stage that, in order to support the substrate, has three defined point-like support elements. The thickness of the substrate is determined using a reference substrate that is first measured. Then the substrate provided for measurement is measured. A data processing element then calculates the corresponding thickness differences from the differences between the reference substrate and the substrate to be measured, and incorporates them into the calculation for further determination of the position of the pattern. This arrangement has a considerable disadvantage, however, in that it is not very flexible, since only fixed mask sizes can be used or measured in this case. It is moreover problematic that if masks with different mask thicknesses need to be measured, the focal plane changes and is no longer located exactly on the surface of the substrate.~~

US Patent 5,671,054 discloses a method and an apparatus for determining the position of patterns on substrates that have a specific thickness. The substrate is placed onto a measurement stage that, in order to support the substrate, has three defined point-like support elements. The thickness of the substrate is determined using a reference substrate that is first measured. Then the substrate provided for measurement is measured. A data processing element then calculates the corresponding thickness differences from the differences between the reference substrate and the substrate to be measured, and incorporates them into the calculation for further determination of the position of the pattern. This arrangement has a considerable disadvantage, however, in that it is not very flexible, since only fixed mask sizes can be used or measured in this case. It is moreover problematic that if masks with different mask thicknesses

need to be measured, the focal plane changes and is no longer located exactly on the surface of the substrate.

Please amend the first paragraph on page 5 as follows:

Located above the substrate is an imaging system 10 of high optical quality that, for focusing, can be adjusted along its optical axis 11 in the Z direction. By way of a beam-splitting mirror 12, on the one hand the light of a light source 13 is introduced into the optical beam path, and on the other hand the imaging rays are directed to a detector device 14. Detector device 14 is, for example, a CCD camera having a high-resolution pixel array. Light source 13 emits in the near UV spectral region. Inserted into granite block 1 is a further illumination device that comprises an adjustable-height condenser 15 and a light source 16. The exit surface of a light guide can also be provided as light source 16. The optical axis of condenser 15 aligns with optical axis 11 of imaging system 10. The purpose of the height adjustment of condenser 15 with light source 16 is to adapt the imaging beam that is to be directed onto patterns 9 to different optical thicknesses of the substrates. The condenser head can, in particular, extend into the open portion of the frame of X/Y ~~carriage 4~~. carriage.

Please amend the third paragraph bridging pages 6 and 7 as follows:

FIG. 5 is the detail view of the region from FIG. 3. Support elements 34 are configured on peripheral rim 32 of opening 30. Support elements 34 lie lower than flat upper surface 42 of substrate holder 8. In the region of support element

34, peripheral rim 32 is equipped with a bevel 44 which thus facilitates the placement of a substrate 20 into opening 30 of substrate holder 8. Support element 34 also defines a flat upper surface 46. A spherical jewel 48, on which substrate & 20 comes to rest with a small rim region, is set into flat upper surface 46.

Please amend page 8 entitled "**PARTS LIST**" as follows:

**PARTS LIST**

- |    |                             |
|----|-----------------------------|
| 1  | Granite block               |
| 2  | Base                        |
| 3  | Base                        |
| 4  | Mirror body                 |
| 5  | Air bearing                 |
| 6  | Air bearing                 |
| 7  | Laser interferometer        |
| 8  | Substrate <u>Holder</u>     |
| 9  | Patterns                    |
| 10 | Imaging system              |
| 11 | Optical axis                |
| 12 | Beam-splitting mirror       |
| 13 | Light source                |
| 14 | Detector device             |
| 15 | Adjustable-height condenser |
| 16 | Light source                |
| 20 | Substrate                   |
| 22 | Rim                         |
| 24 | Orifice                     |
| 26 | Spacer pin                  |
| 28 | Spherical protrusion        |
| 30 | Opening                     |
| 32 | Peripheral rim              |
| 34 | Support element             |
| 35 | Reflective elements         |
| 36 | Further openings            |
| 38 | Code                        |

|     |                      |
|-----|----------------------|
| 40  | Reference marks      |
| 42  | Flat upper surface   |
| 44  | Bevel                |
| 46  | Flat upper surface   |
| 48  | Spherical jewel      |
| 50  | Circular depression  |
| 52  | Limit stop edge      |
| 100 | Measuring instrument |